

In the Claims:

Please amend the claims as follows:

1.(amended) An apparatus for processing a substrate, the apparatus comprising:

- (a) a chamber; and
(b) a pump adjacent to the chamber, the pump having an inlet

connected to the chamber to evacuate gas in the chamber and an outlet that exhausts the evacuated gas to atmospheric pressure.

7.(amended) An apparatus according to claim 1 further comprising a pressure controller to control the pressure of the gas in the chamber by adjusting a speed of the pump.

9.(amended) An apparatus for processing a substrate, the apparatus comprising:

- (a) a load-lock chamber comprising an enclosure; and
(b) a pump adjacent the load-lock chamber, the pump having an inlet

connected to the load-lock chamber to evacuate gas from the load-lock chamber and an outlet that exhausts the gas to atmospheric pressure.

15.(amended) An apparatus according to claim 9 further comprising a pressure controller to control the pressure of the gas in the load-lock chamber by adjusting a speed of the pump.

23.(amended) An apparatus according to claim 16 further comprising a pressure controller to control the pressure of the process gas in the process chamber by adjusting a speed of the pre-vacuum pump.

24.(amended) An apparatus for processing a substrate, the apparatus comprising a chamber, a pump capable of operating at different speeds, a pump controller to control the speed of the pump, and a pressure controller to control a gas pressure of a gas in the chamber by providing a signal in relation to the gas pressure to the pump controller that

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changes the speed of the pump in relation to the signal from a first pump speed at which the gas in the chamber is evacuated at a first volumetric flow rate to a second pump speed at which the gas in the chamber is evacuated at a second volumetric flow rate.

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47.(amended) An apparatus according to claim 38 further comprising a pressure controller to control the pressure of gas in the chambers by adjusting a speed of the pump.

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55.(amended) An apparatus according to claim 48 further comprising a pressure controller to control the pressure of gas in the chambers by adjusting a speed of the pump.

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64.(amended) An apparatus according to claim 56 further comprising a pressure controller to control the pressure of gas in the chambers by adjusting a speed of the pump.

65.(amended) An apparatus for processing a substrate, the apparatus comprising:

- (a) a chamber capable of holding a substrate and processing the substrate in a gas;
- (b) a pump capable of evacuating a gas from the chamber, the pump capable of changing its speed; and
- (c) a pump controller adapted to provide a signal to the pump to vary the speed of the pump from a first pump speed at which the gas in the chamber is evacuated at a first volumetric flow rate to a second pump speed at which the gas in the chamber is evacuated at a second volumetric flow rate to control the rates of evacuation of the gas in the chamber to reduce condensation of moisture in the chamber.

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72.(amended) An apparatus according to claim 65 further comprising a pressure gauge to measure a pressure of the gas in the chamber and provide a signal to the pump controller and wherein the pump controller changes the speed of the pump in relation to the signal.

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84.(amended) An apparatus for processing a substrate, the apparatus comprising:

- (a) a chamber capable of holding a substrate and processing the substrate in a gas;
- (b) a pump capable of evacuating a gas from the chamber, the pump being capable of operating at different speeds; and
- (c) means for changing a speed of the pump from a first pump speed at which the gas in the chamber is evacuated at a first volumetric flow rate to a second pump speed at which the gas in the chamber is evacuated at a second volumetric flow rate to control the rates of evacuation of the gas to reduce condensation of moisture in the chamber.

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92.(amended) An apparatus for processing a substrate, the apparatus comprising:

- (a) a chamber capable of holding a substrate and processing the substrate in a gas; and
- (b) a pump having an inlet connected to the chamber via a foreline for evacuating gas in the chamber, the foreline having an internal surface area of less than about 0.4 m^2 for a length of about 2 m, and the pump having an outlet that exhausts the evacuated gas to atmospheric pressure.

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97.(amended) An apparatus for processing a substrate, the apparatus comprising:

- (a) a chamber capable of holding a substrate; and
- (b) a pump having an inlet connected to the chamber via a foreline for evacuating gas in the chamber, the foreline having an internal surface area of less than about 0.4 m^2 , and the pump having an outlet that exhausts the evacuated gas to atmospheric pressure.